

ABSTRACT OF THE DISCLOSURE

5 A method for cleaning a process chamber, comprising the
steps of introducing at least one cleaning gas to the process chamber;
and employing a rapid heating module located in the process chamber,
wherein the rapid heating module increases the temperature of
chamber parts and improves the surface temperature uniformity of
chamber parts when the module is turned on, thereby assisting the
10 cleaning activity of the cleaning gas such that the process chamber is
cleaned.